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DEMARK OFFICE

| Application Serial No   |
|---|
| Filing Date April 13, 1998                                      |
| nventor Pai-Hung Pan  |
| Assignee Micron Technology, Inc.                                |
| Group Art Unit  |
| Examiner  |
| Attorney's Docket NoMI22-898                                    |
| Title: Semiconductor Processing Methods of Forming a Conductive |
| Gate and Line   |

## RESPONSE TO JUNE 20, 2000 OFFICE ACTION

To:

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Assistant Commissioner for Patents

Washington, D.C. 20231

From:

Bernard Berman (Tel. 509-624-4276; Fax 509-838-3424)

Wells, St. John, Roberts, Gregory & Matkin P.S.

601 W. First Avenue, Suite 1300

Spokane, WA 99201-3828

Sir:

Responsive to the Office Action dated June 20, 2000, applicant requests reconsideration of the above referenced application in view of the amendments and remarks that follow:

RECEIVED

TECHNOLOGY CENTER 2800

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